LGAD sensors & plans for a beam telescope timing layer

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The need for new timing detectors

Experimental environments are evolving

 \rightarrow Include track timing to address new challenging conditions

Time information complements spatial information:

- Timing layer: timing in event reconstruction
- "4D" tracking: timing at each point along the track

Example goals/requirements: HL-LHC 50 ps, HADES 60 ps, FCC-hh 10 ps

Example





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HEP detector R&D: dedicated beam tests for conceptual / technical design, calibrations, commissioning, ... \rightarrow DESY II Testbeam Faciliy

Integral part of test beam infrastructure: Beam Telescopes

- \rightarrow EUDET-type telescopes: 6 layers of MIMOSA26 pixel sensors
 - Monolithic Active Pixel Sensor
 - 1152 × 576 pixels, pitch: 18.4 μm
 - Measured intrinsic sensor resolution: $\sigma \cong 3 \, \mu m$
 - Rolling shutter readout, readout cycle 115 μs







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"No" time resolution \rightarrow upgrade needed to meet requirements of future detector test campaigns





Upgrade Plans



Add faster device for time stamping the tracks \rightarrow timing layer

- Short term: existing sensor as intermediate solution
 Timepix3
 - Already existing and functional
 - Timestamps $\mathcal{O}(1 \text{ ns})$
- Long term: develop next-generation timing layer
 - ► LGAD → this talk
 - Allow for picosecond-timing
 - Requires R&D
 - Dedicated ROC? Start with Timepix3 for first prototypes



[CERN-PHOTO-201702-048-4]



[doi.org/10.1140/epja/s10050-020-00186-w]



Low Gain Avalanche Diodes

Ultra Fast Silicon Detectors optimised for timing measurements:

- Thin multiplication layer
- \rightarrow High field
- \rightarrow Increase signal by factor ${\sim}10$



LGADs are routinely produced in various sizes and pad numbers (e.g. by CNM, FBK, HPK)

$\mathcal{O}(30\,\text{ps})$ time resolution possible



- Each step in the read-out process
- Anything that changes the shape of the signal

$$\sigma_t^2 = \sigma_{\text{TimeWalk}}^2 + \sigma_{\text{LandauNoise}}^2 + \sigma_{\text{Distortion}}^2 + \sigma_{\text{Jitter}}^2 + \sigma_{\text{TDC}}^2$$
arXiv:1704.08666

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Variation in time of arrival due to different signal amplitudes

Compensation: Constant Fraction Triggering or amplitude-based correction (TOT)



Time walk effect OE 56(3), 031224 (2017)

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Caused by inhomogenities in drift velocity & weighting field

Compensation: saturated drift velocity & optimised geometry ("parallel plate") Time-to-digital converter contribution $\Delta T / \sqrt{12}$ (bin width)

in most cases small contribution

- Each step in the read-out process
- Anything that changes the shape of the signal

$$\sigma_t^2 = \sigma_{\text{TimeWalk}}^2 + \sigma_{\text{LandauNoise}}^2 + \sigma_{\text{Distortion}}^2 + \sigma_{\text{Jitter}}^2 + \sigma_{\text{TDC}}^2$$

Energy deposit Current fluctuations due to signal shape variations for MIP ionization

Time-Of-Arrival variations due to noise

- sensor noise
- electronics noise
- slew rates (dV/dt)

arXiv:1704.08666

= the main contributors \rightarrow low gain, thin detectors (see next slides)

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Why Low Gain?

High gain has many drawbacks: risk of breakdown, power consumption, higher noise

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"Excess Noise Factor" (F): additional noise induced by the multiplication mechanism (gain not constant \rightarrow additional fluctuations in current)
F \sim G^{x}
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signal after multiplication: multiplied by G current noise increases with \sqrt{F}

 \rightarrow S/N ratio deteriorates at higher gain

For a given ENF, there is an optimum gain (10 \sim 30)





Why thin sensors?

Current fluctuations are due to statistics of MIP ionization

> For a fixed gain: amplitude of the signal independent of thickness d:

 $I_{max} \sim n_{eh-initial} \, G \, q \, v_{sat}$

arXiv:1704.08666



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Irradiation causes three main effects:

- Decreased charge collection efficiency
- Increased leakage current
- Change of doping profile

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Deactivation of p-doping by Boron removal \rightarrow Gain reduction due to irradiation



Lots of R&D ongoing, different doping profiles and ion implants:

Defect Engineering of the gain implant

- Carbon co-implantation in gain layer volume
- Boron as gain layer implant

Modification of gain layer profile

 Narrower doping layer with higher initial doping

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Ultra-fast silicon detectors - performance

Example: UFSD from Hamamatsu

- LGAD with 50 µm thickness
- > Value of gain ~20
- > 30 ps time resolution



Example: Irradiation study for HGTD

- ► LGAD with 45 55 µm thickness
- Different vendors/implantations
- > \sim 40 ps time resolution after irradiation



R&D Challenge: Fill Factor

Segmentation to improve spatial resolution

- Inter-pixel region: isolation and termination structures (p-stop, Junction Termination Extension, virtual GR)
- Carriers generated in this area not multiplied
- Interpad regions with no gain $\mathcal{O}(\approx 30 \, \mu m \text{ to } 70 \, \mu m)$
- \rightarrow R&D challenge:

Segmentation with improved fill factor

Several technology options:

Trench-isolated LGAD

Inverse LGAD

Resistive AC-Coupled LGAD

(see talk N. Cartiglia at last week's instrumentation seminar)

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Standard segmentation



[[]G. Paternoster, 35th RD50 workshop, Nov 2019]

TI-LGAD

Trench isolation:

- JTE and p-stop replaced by trench to isolate the pixels
- Filled with Silicon Oxide
- Typical trench width < 1 µm much smaller wrt. JTE and p-stop
 - \rightarrow smaller no-gain region



1 Trench Layout (trench grid)



2 Trenches Layout





[G. Paternoster , 35th RD50 workshop, Nov 2019] Universität Hamburg A. Vauth | SiDet meeting, 10.3.2021 | LGADs for Beam telescope timing

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Layout	Nominal no-gain	Effective gain-loss
1 Trench	~ 4 um	~6 um
2 Trenches	~ 6 um	~3 um

[G. Paternoster , 35th RD50 workshop, Nov 2019]

Trade-off between minimizing gain-loss region and reducing E-field at the border





Comparison of FBK productions: UFSD3 vs Trench-Isolated

iLGAD

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Inverse LGADs:

- No segmentation of the multiplication layer
- Hole collection
- Complex double side process (first generation)



LGAD TECHNOLOGY

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iLGAD

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Jniversität Hamburg

Inverse LGADs:

- No segmentation of the multiplication layer
- Hole collection
- Trenches to isolate the active area (third generation)
- Single-side process





[D. Flores, SIMDET '16, Sep 2016]

iLGAD for Timing

To use iLGADs for timing applications \rightarrow Reduce the thickness of the detector CNM: fabrication with two different approache

- 1. Epitaxial wafer + epitaxial multiplication
- 2. Si-Si wafers + implanted multiplication



> Trench-isolated LGADs: part of RD50 run @ FBK Pixel pitch: $55 \,\mu m \times 55 \,\mu m$, number of pixels 55×55 Production to finish end of this month

Inverse LGADs: part of RD50 run @ CNM
 Pixel pitch: 55x55 µm², number of pixels 256x256
 Mask design/fabrication ongoing,
 Production to be finished in September

Other ingredients for improved timing? Trigger Logic Unit, DAQ software \rightarrow AIDA-2020 TLU, EUDAQ 2





Summary & Outlook

- Low Gain Avalanche Diodes to measure both time and space - with improved signal-to-noise ratio
- For timing: 30-50 μm thickness, gain (*O*)(10)
- R&D ongoing on
 - radiation hardness (doping profile, ion implantats)
 - segmentation (Trench / Resistive AC / i-LGAD)
 - and more (uniformity, electronics, ...)
- More and more R&D on fast timing detectors → growing need for timing layer to test them



\rightarrow LGAD layer for beam telescopes for the next decade of successful testbeam operation

Backup Slides

iLGAD Third Generation (iLG3): Fabrication Process

We are planning to carry out this fabrication with two different approaches:

- Epitaxial wafer + epitaxial multiplication 1.
- 2. Si-Si wafers + implanted multiplication

(2)(1)Dose/energy multiplication layer is adapted to the Si-Si 4" high resistivity >10kOhm · cm p-type multiplication laver thermal process p-doped 285 µm wafer implantation CNM (3) (4) Wafer reduction to 50 µm After (4), the profile is the same as standard I GAD runs. This is the Foundry starting point for the fabrication. Low resistivity n-doped wafer Low resistivity n-doped wafer Thermal process Si-Si



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Example of signal sharing

